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U.S. PTO
10/30/01

PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL. NUM	FILING DATE	10/30/01	10/30/01	CLAS	SUB CLAS	GAU	EXAMINER
1001805	10/30/01	430				1752	

**APPLICANTS: Lin Shun-Li; Hsu Wei-Hua;

yet

**CONTINUING DATA VERIFIED:

None yet

** FOREIGN APPLICATIONS VERIFIED:

TAIWAN 90118271 07/29/2001

yet

PC-PUB	DO NOT PUBLISH <input checked="" type="checkbox"/>	RE-1010 <input type="checkbox"/>	ATTORNEY DOCKET NO
Foreign priority claimed		Yes <input type="checkbox"/> No <input checked="" type="checkbox"/>	JCLA7245
35 UCC 119 conditions met		Yes <input type="checkbox"/> No <input checked="" type="checkbox"/>	
Verified and Acknowledged Examiner's initials <i>not</i>			
TITLE: Photoresist with adjustable polarized light reaction and photolithography process using the photoresist			
US DEPT OF COMMERCE & TRADEMARKS 1000			

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED	
Amount Due	Date Paid		Total Claims	Print Claim for O.G
ISSUE FEE		DRAWING		
		Sheets Drwg.	Figs. Drwg.	Print Fig.
TERMINAL DISCLAIMER		Application Examiner		
PREPARED F R ISSUE		WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368. Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.		

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